IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application	
Inventor(s):	Patrick P. Naulleau
SC/Serial No.:	09/981,500
Confirm. No.:	6932
Filed:	October 16, 2001
Title:	A HOLOGRAPHIC ILLUMINATOR FOR SYNCHROTRON-BASED PROJECTION LITHOGRAPHY SYSTEMS

PATENT APPLICATION

Art Unit: 2872
Examiner: Lavarias, Arnel C.

Customer No. 23910

#7|A
T.4326
2-4-03

CERTIFICATE OF MAILING UNDER 37 C.F.R. § 1.8

I hereby certify that this correspondence is being deposited in the United States Postal Service with sufficient postage as first class mail in an envelope addressed to Commissioner for Patents, Washington, DC 20231, on January 24, 2003.

_____(Attorney Signature)
Charles H. Jew, Reg. No. 34,192
Signature Date: January 24, 2003

AMENDMENT/RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. § 1.111

Commissioner for Patents
Washington, DC 20231

Sir:

This AMENDMENT/RESPONSE is in reply to the Office action mailed October 24, 2002. No fee is due in connection with this response.

Amendments

Please amend the above-identified application as follows:

In the Specification:

Please amend the paragraph on Page 2, beginning at line 11 to read as follows:

Projection lithography is a powerful and essential tool for microelectronics processing and has supplanted proximity printing. "Long" or "soft" x-ray (a.k.a. Extreme UV) (wavelength range of 10 to 20 nm) are now a the forefront of research in efforts to achieve smaller transferred feature sizes. With projection photolithography, a reticle (or mask) is imaged through a reduction-projection (demagnifying)